

S/N : 10/661,048
Applicant : Qun Ying Lin
Reply to the Office action (ROA # 2) dated July 12, 2005

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Amendments to the specification

Please replace the paragraph starting on specification p. 2, line 21, with the following amended paragraph:

US 6,482,554(Matsunuma) shows a ~~for~~ a method for a dual damascene pattern comprising: exposing two photoresist layers using a grey (tri-tone) mask.